



IMN-KOLLOQUIUM

Mittwoch, 10. Mai 2023 um 13:00 Uhr im Feynmanbau Raum 115

Dr.-Ing. Martin Knaut

Technische Universität Dresden, Institut für Halbleiter- und
Mikrosystemtechnik, Professur für Nanoelektronik

Atomic Layer Processing – An Overview

Atomic Layer Deposition is a versatile deposition process offering excellent control over film properties and outstanding reproducibility. Especially atomic layer deposition is widely used besides its main application in the microelectronics industry. This talk should give an overview about the basic principles of atomic layer deposition and etching, the applied techniques, tools and processes and current research topics. Further, it should demonstrate how ALD or ALE processes are developed and how process parameters can affect film growth or etch and other film properties.

Vortragssprache: englisch